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Journal Name

ARTICLE

6 Band gap engineering of graphenylene by hydrogenation and 7 halogenation: a density functional theory study

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9 Graphenylene, a new form of two-dimensional (2D) carbon allotrope consisting of non-delocalized sp²-carbon atoms, has
10 aroused considerable interest recently due to its thermodynamic stability and porous structure. In this work, density
11 functional theory is used to investigate the hydrogenation and halogenation of graphenylene. The adsorption stability of
12 hydrogen and halogen atoms on graphenylene is discussed at different concentrations of adsorbate atoms. The electronic
13 structures of functionalized graphenylenes show that by controlling the concentration of adsorbate atoms, the band gap
14 of graphenylene could be tuned in a wide range, from 0.075 to 4.98 eV by hydrogenation and 0.024 eV to 4.87 eV by
15 halogenation.

16 1. Introduction

17 Graphene, an atomic monolayer of graphite consisting of sp²
18 carbon atoms that are arranged in a honeycomb lattice,¹ is a
19 promising 2D material for applications in many emerging
20 technologies.^{2,3} It has attracted tremendous attention in the
21 last decade because of its peculiar electronic and physical
22 properties, such as the Dirac cone structure, exceptional
23 carrier mobility,^{4–6} high thermal conductivity⁷ and high
24 mechanical strength.^{8,9} However, graphene is intrinsically
25 metallic with zero-gap, which hinders its application in
26 based electronic devices. Therefore, much effort has been
27 devoted to engineer its band gap. Chemical functionalization is
28 an effective way to modify the electronic properties of
29 graphene. Recent researches have demonstrated that
30 hydrogenation and fluorination can tune the band gap of
31 graphene up to ~ 5.4 and ~ 7.0 eV respectively,^{10–15} for
32 example, Gao et al.¹⁵ theoretically predicted that the band gap
33 of hydrogenated graphene with paired hydrogen vacancies can
34 be tailored continuously from 0 to 4.66 eV, depending on
35 hydrogen coverage and configurations. But this tuning has
36 limitation, since hydrogen or fluorine atoms adsorbed on
37 graphene were found to tend to aggregate with each other in

38 experiments. Recent experimental studies showed that the
39 functionalization level of graphene can be precisely controlled
40 by using a reactive ion etching plasma¹⁶ or the scanning probe
41 technique.¹⁷ These experimental evidences will lead to the
42 development of graphene-based electronic devices.

43 On the other hand, it is well known that carbon atoms have
44 the ability to exist in different hybridizations. Thus, searching
45 new forms of 2D carbon allotropes has aroused considerable
46 interest from both academe and industry. Many of carbon
47 allotropes such as graphyne and graphdiyne have been
48 predicted to have unique electronic and mechanical
49 properties.^{18,19} Graphenylene, a new full sp²-hybridized carbon
50 network, possesses the same point group, D_{6h}, as graphene.
51 The structure, consisting of hexatomic and tetraatomic rings
52 with porous structures, was firstly proposed by Balaban²⁰ and
53 the properties have been investigated.^{21–23} In one recent
54 paper, Zhi et al.²⁴ studied the structural and electronic
55 properties of graphenylene by first-principles calculation. They
56 predicted that graphenylene is a true minimum on the
57 potential energy surface and the first example of a non-
58 delocalized sp²-carbon structure. More specifically,
59 graphenylene is predicted to be a semiconductor with a
60 narrow direct band gap of 0.025 eV. In addition, ab initio
61 quantum molecular dynamics calculation²⁵ showed that
62 graphenylene could be formed by selective dehydrogenation
63 of porous graphene, which implies that the possibility of the
64 synthesis of graphenylene.

65 Lee et al.^{26–28} recently reported the first-principles studies on
66 tailoring the band gaps of two carbon allotropes, graphyne and
67 graphdiyne, by hydrogenation and halogenation. Their
68 calculations showed that different from the case occurring on

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graphene, hydrogen or halogen atoms preferentially adsorb on carbon atoms with no clustering. Therefore, it is natural to inquire whether the band gap of graphenylene can also be modified by hydrogenation and halogenation, and what size the band gap can be opened. Considering the unique electronic and structural properties as well as the potential applications in semiconductor-based electronic devices and energy storage,²⁹ in the present work, we performed a systematic density functional theory (DFT) study to investigate the hydrogenation and halogenation of graphenylene. The geometrical and electronic properties of hydrogenated and halogenated graphenylenes were obtained. The change in band gaps of functionalized graphenylenes depending on the type and the concentrations of adsorbates is discussed. The results show that by controlling the concentration of adsorbate atoms, the band gap of graphenylene could be tuned up to 4.98 eV by hydrogenation and 4.87 eV by halogenation, comparable to band gap tuning of 4.5 (3.04) and 3.0 (5.20) eV by hydrogenation and halogenation of graphyne^{26,28} (graphdiyne²⁷). The analysis of the absolute energies of the edge states of functionalized graphenylenes demonstrates that they may have application potentials in photocatalysis. Our aim is to provide a comprehensive understanding for the implications of graphenylene for potential 2D device applications based on the predicted tunable band gap trend.

2. Methodology

All the first-principles calculations were performed based on periodic density functional theory using Vienna Ab-Initio Simulation Package (VASP)³⁰ with a projector augmented wave (PAW)³¹ approach. The electron exchange and correlation were treated by the generalized gradient approximation (GGA)

with Perdew-Burke-Ernzerhof (PBE)³² functional. Neighboring slabs are separated by a vacuum region of about 20 Å along the z-direction to avoid interactions between them. Monkhorst-Pack³³ $8 \times 8 \times 1$ k-point mesh was used for structure optimizations. The cutoff energy in the plane-wave expansion was set to 900 eV. To obtain accurate band gap values, Heyd-Scuseria-Ernzerhof (HSE)³⁴ hybrid functional was also used to calculate the band structures.

3. Results and discussion

Graphenylene is composed of cyclohexatriene units with 12 carbon atoms in one unit cell. The optimized structure of graphenylene in a 2×2 supercell is shown in Fig. 1a. The calculated lattice parameters of graphenylene are $a = b = 6.764$ Å. In one hexatomic ring of graphenylene there are two different C-C bonds, one C-C double bond and one C-C single bond. Adding the C-C single bond between two neighboring hexatomic rings, there are totally three different C-C bonds in graphenylene. The bond length of the double bond is 1.366 Å and the bond lengths of the other two single bonds are 1.471 and 1.479 Å, respectively. All these obtained geometrical parameters are in good agreement with previous results.²⁴ In present work, we study both hydrogenated and halogenated graphenylene, CM_x , where M presents hydrogen or halogen (fluorine, chlorine, bromine and iodine) atoms, and x is the concentration of the adsorbates. For the hydrogenation and halogenation of graphenylene, the hydrogen or halogen atoms can bind to each sp^2 carbon atom of one double bond with one atom above the graphenylene plane and the other below the plane. There are totally six double bonds in one graphenylene unit cell, thus the concentration of the adsorbate atoms x equals to 0.17, 0.33, 0.50, 0.67, 0.83 and 1.00.

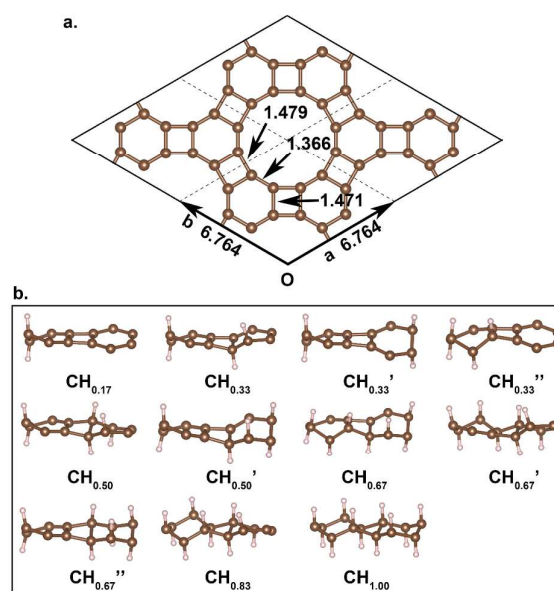


Figure 1. (a) Two dimensional structure of pristine graphenylene in a 2×2 supercell. The unit of lattice parameters and bond lengths is angstrom. (b) The structures of hydrogenated graphenylene in one unit cell at various

The optimized structures of hydrogenated graphenylene⁴⁵ in one unit cell at various concentrations are shown in Fig. 1⁴⁶. The six double bonds in one graphenylene unit cell are⁴⁷ identical, thus at $x = 0.17, 0.83$ and 1.00 the structures⁴⁸ are unique, while there are⁴⁹ three, two and three kinds of structures (labeled 50 apostrophe) at the concentrations of $0.33, 0.50$ and 0.67 , respectively, based on the different adsorption sites of hydrogen atoms. Through hydrogenation, the hybridization of carbon atoms is changed from sp^2 to sp^3 . The structures vary from strictly two dimensional to corrugate gradually with the increase of the hydrogen concentration. In $CH_{1.00}$, both the two hexatomic rings are in chair conformation. The in plane lattice constant of graphenylene was decreased by $0.040, 0.125$ and 0.009 \AA at $x = 0.17, 0.33$ and 0.67 respectively, while it was increased by $0.013, 0.120$ and 0.176 \AA at $x = 0.50, 0.83$ and 1.00 , respectively. Lattice constants a and b are always equivalent at each concentration. The structures of halogenated graphenylenes are studied similarly. Through calculation we found that if the concentration x and the locations of adsorbate atoms are the same, the optimized structures of halogenated graphenylenes are almost the same as hydrogenated graphenylenes, except that the C-M bond lengths increase as the atomic number increases from hydrogen to iodine. For example, the calculated C-M bond lengths in $CM_{0.17}$ are $1.102, 1.402, 1.812, 2.000$ and 2.224 \AA for C-H, C-F, C-Cl, C-Br and C-I bonds respectively. The lattice constants of halogenated graphenylenes decrease at lower concentrations, $x = 0.17$ and 0.33 , while increase at higher concentrations $x = 0.50 \sim 1.00$. The optimized structures of halogenated graphenylenes and the lattice constants of functionalized graphenylenes are shown in Supporting Information. In the following sections, only the most stable structures of hydrogenated and halogenated graphenylenes at each concentration are further studied to understand the thermodynamic and electronic properties of chemically functionalized graphenylenes.

The binding energy of per adsorbate atom in CM_x is defined as

$$E_{binding}^x(M) = (E_{CM_x} - E_{graphenylene} - n \cdot E_M) / n$$

where E_{CM_x} is the total energy of functionalized graphenylene CM_x , $E_{graphenylene}$ is the total energy of pristine graphenylene, E_M is the energy per M atom of an M_2 molecule in vacuum, and n is the number of adsorbed M atoms per unit cell for a given x . The calculated binding energies as a function of the

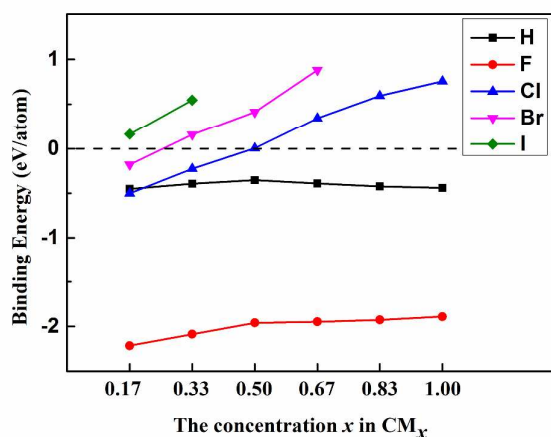


Figure 2. The binding energies of hydrogen and halogen atoms as a function of the concentration x .

concentration x are presented in Fig. 2. Seen from Fig. 2, the binding of fluorine to graphenylene is always the most stable at each concentration, which can be attributed to the strongest electronegativity and small ionic radius of fluorine. For example, the calculated binding energies are $-0.45, -2.21, -0.50$ and -0.18 eV/atom for H, F, Cl and Br, respectively, at $x =$

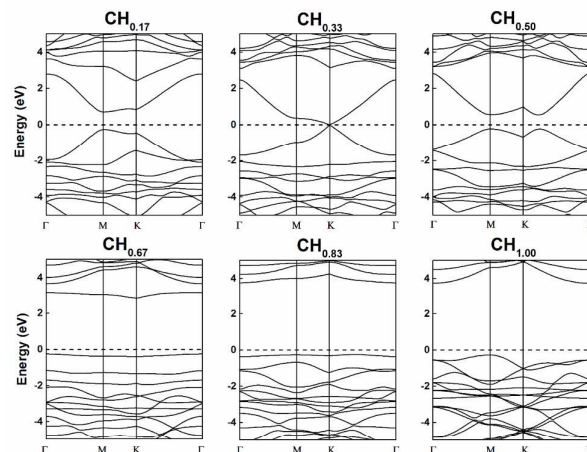


Figure 3. The PBE band structures of hydrogenated graphenylenes at different hydrogen concentration x . The Fermi levels are shown by dashed lines.

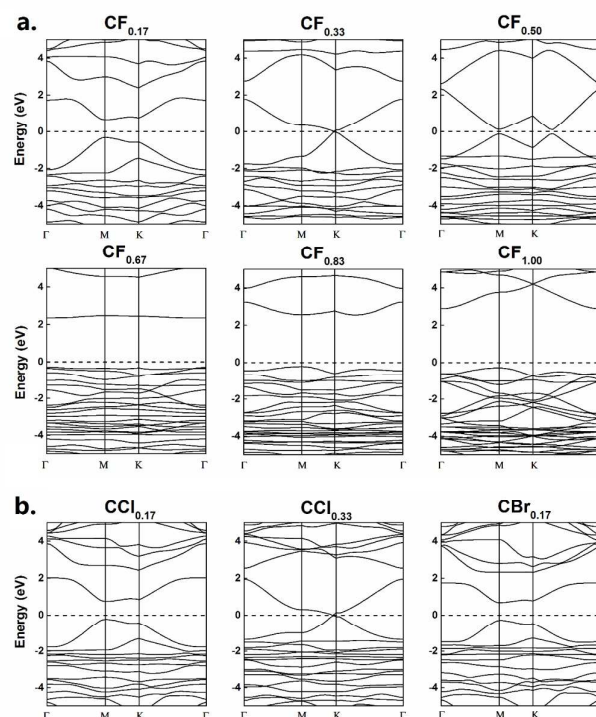


Figure 4. (a) The PBE band structures of fluorinated graphenylenes at different fluorine concentration x . (b) The PBE band structures of halogenated graphenylenes $CCl_{0.17}$, $CCl_{0.33}$ and $CBr_{0.17}$. The Fermi levels are shown by dashed lines.

1 0.17. As the concentration x increases, the binding energies of

hydrogen are nearly unchanged and the binding energies of fluorine slightly increase, while the changes in the binding energies of chlorine and bromine atoms are much larger. It is seen that the adsorption processes become endothermic when the concentration x of chlorine and bromine is larger than 0.33 and 0.17, respectively, and for iodine, the calculated binding energies at any concentration are all positive, indicating that the adsorption of Cl, Br and I at the concentrations is unstable. In addition, the change trend of the binding energies as a function of the concentration x in Fig. 3 indicates the repulsive interaction between adsorbate atoms (hydrogen/halogen atoms). As a result, the clustering of hydrogen and halogen atoms is energetically unfavorable on graphene, making band gap tunable by hydrogenation and halogenation. The adsorption structure features of hydrogenated and halogenated graphenylenes are very similar to previous studies on functionalized graphene and graphdiyne.^{26,27}

The electronic properties of hydrogenated and halogenated graphenylenes are studied. The PBE band gap of pristine graphene was calculated to be 0.039 eV, which is in good agreement with the previously reported value 0.025 eV.²⁴ The PBE band structures of hydrogenated graphenylene at different hydrogen concentrations are presented along the high symmetry lines of the Brillouin zone in Fig. 3. At

concentrations of $x = 0.17$, 0.33 and 0.50, the stable hydrogenated graphenylenes have direct band gaps of 0.96, 0.021 and 0.77 eV, with the valence band maximum (VBM) and conduction band minimum (CBM) located at the M point, K point and between K and Γ , respectively; while at $x = 0.67$, 0.83 and 1.00, three indirect band gaps of 3.08, 4.01 and 4.01 eV, respectively, are obtained. In the band structures of $\text{CH}_{0.17}$, $\text{CH}_{0.33}$ and $\text{CH}_{0.50}$, the bands around both VBM and CBM exhibit very large dispersion, indicating higher mobilities of both electrons and holes; on the contrary, at higher concentrations ($x > 0.50$), the bands of VBM and CBM become much flatter, implying these hydrogenated graphenylenes may have lower mobilities of both electrons and holes.

In Fig. 4a, the band structures of fluorinated graphenylenes are illustrated. It is shown that the characteristics of these band structures are very similar with that of hydrogenated graphenylenes. At $x = 0.17$ and 0.33, two semiconductors with direct gaps of 0.99 and 0.024 eV, respectively, are obtained. The VBM and CBM positions of $\text{CF}_{0.17}$ are located at the M point, while those of $\text{CF}_{0.33}$ are located to the left of the K point. $\text{CF}_{0.50}$ is a semiconductor with an indirect gap of 0.24 eV. Its VBM is located at the M point and its CBM is located between the K and Γ point. At higher concentrations ($x > 0.5$), the band gaps of fluorinated graphenylenes are calculated to be 2.65, 2.77 and 3.17 eV. As the case in hydrogenated graphenylenes, the mobilities of electrons and holes of fluorinated graphenylenes may be higher at the F concentrations from $x = 0.17$ to 0.50, while much lower at $x = 0.67$, 0.83 and 1.00. In Fig. 4b, the band structures of $\text{CCl}_{0.17}$, $\text{CCl}_{0.33}$ and $\text{CBr}_{0.17}$ are illustrated. Clearly, the band structures of CCl_x and CBr_x show similar features with those of CF_x . They are predicted to be semiconductors with direct band gaps of 0.98, 0.026 and 0.97 eV, respectively.

The calculated PBE band gaps of hydrogenated and halogenated graphenylenes as a function of the concentration x are presented in Fig. 5a. Since the local and semilocal functionals such as PBE functional are known to underestimate the band gaps, and hybrid DFT functionals such as HSE in general describe quite accurate band gaps when compared with the experimental values.³⁴ Therefore, HSE functional is also employed to predict the band gaps of functionalized graphenylenes. The HSE band gaps of hydrogenated and halogenated graphenylenes are shown in Fig. 5b. The HSE band gap of graphene is 0.48 eV, thus the band gap of pristine graphene is underestimated by 0.44 eV using the PBE. From Fig. 5a-b, it is seen that the functionalized graphenylenes exhibit a wide band gap semiconducting behavior and both PBE and HSE gaps change in the similar trend as a function of the concentrations. At the $x = 0.17$ concentration, the band gap is enlarged compared to that of pristine graphene, while it decreases to a much narrower gap at $x = 0.33$. As the concentration x increases from $x = 0.33$ to 1.00, the band gaps increase and the gap values of hydrogenated graphenylenes are larger than those of fluorinated graphenylenes. For example, at $x = 0.50$, the HSE band gap of hydrogenated graphene is 1.37 eV, which is 0.74 eV larger than that of fluorinated graphene.

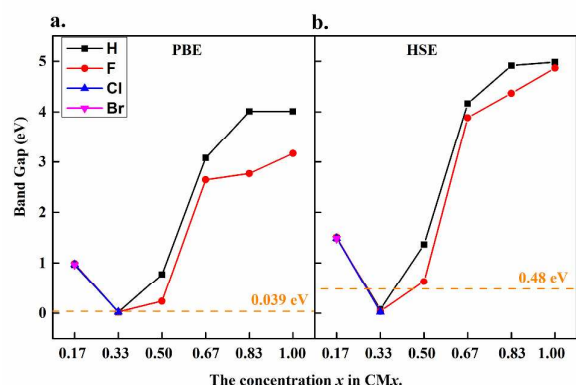


Figure 5. The calculated PBE (a) and HSE (b) band gap values of functionalized graphenylenes as a function of the concentration x . The orange dashed lines and numbers indicate the band gap values of pristine graphene.

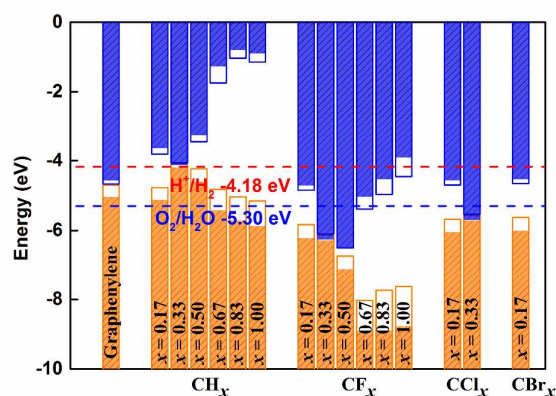


Figure 6. Band edges of graphene and functionalized graphenylenes relative to the vacuum level. The blue and brown lines represent the PBE results, while the columns filled by blue and brown colors represent the HSE results. The dashed lines indicate the water redox potentials.

Therefore, one can find that the band gap of graphenylene can be tuned in a wide range, 0.075 to 4.98 eV by hydrogenation and 0.024 eV to 4.87 eV by halogenation.

At last, the absolute energies of the edge states of hydrogenated and halogenated graphenylenes at various concentrations are studied, because the VBM and CBM positions are important for the application of 2D material photocatalyst for water splitting and organic pollutant degradation. By aligning the average electrostatic potentials of the 2D sheets with that of the vacuum, the VBM and CBM positions calculated by both HSE and PBE are plotted in Fig. 6. Note that at the $x = 0.17$ and 0.33 concentrations, the band edge positions of fluorinated graphenylenes are very close to those of chlorinated and brominated graphenylenes, which are quite different from those of hydrogenated graphenylenes, although their band gaps are almost the same. Generally speaking, both CBM and VBM energies of fluorinated (and halogenated) graphenylenes are lower than those of hydrogenated graphenylenes, which means that fluorinated graphenylenes possess larger ionization energies and electron affinities. As an example, the redox potentials of water are also given in the figure. It is seen that the band edges of $\text{CH}_{0.83}$, $\text{CH}_{1.00}$ and $\text{CF}_{1.00}$ satisfy the band edge requirement, straddling well with the water redox potentials as shown in Fig. 6. As a consequence, the reduction and oxidation processes of water are thermodynamically favorable. For $\text{CH}_{0.67}$, $\text{CH}_{0.83}$, $\text{CH}_{1.00}$ and $\text{CF}_{1.00}$, their CBM are 2.91, 3.38, 3.29 and 0.26 eV more positive than the reduction potential of H^+/H_2 , and their VBM are 0.13, 0.41, 0.57 and 3.48 eV more negative than the oxidation level of $\text{O}_2/\text{H}_2\text{O}$. It is seen that $\text{CH}_{0.83}$ has the largest energy difference between CBM and the reduction potential of H^+/H_2 and $\text{CF}_{1.00}$ has the largest energy difference between VBM and the oxidation potential of $\text{O}_2/\text{H}_2\text{O}$. As stated in previous papers,^{36,37} the larger energy difference between CBM/VBM and the water reduction/oxidation potential, the higher the reducing/oxidizing power. Therefore, $\text{CH}_{0.83}$ and $\text{CF}_{1.00}$ possess the strongest reducing and oxidizing capability, respectively. For the rest obtained functionalized graphenylenes, $\text{CH}_{0.17}$ and $\text{CH}_{0.50}$ have favorable CBM positions for hydrogen production, while $\text{CF}_{0.17}$, $\text{CF}_{0.67}$, $\text{CF}_{0.83}$, $\text{CCl}_{0.17}$ and $\text{CBr}_{0.17}$ possess good enough VBM positions for oxygen production. Above all discussions, the functionalized graphenylenes may have application potentials in catalysis.

4. Conclusions

In this work, the hydrogenation and halogenation of graphenylene are studied using first-principles calculations. Hydrogen and fluorine atoms preferentially bind to graphenylene to form sp^3 hybridized bonds at all concentrations considered, the adsorption of chlorine, bromine and iodine is favorable only at lower concentrations, while iodine atoms are unstable at any concentrations. The change trend of the calculated binding energies indicated the clustering of hydrogen and halogen atoms on graphenylene is not preferable, which makes band gap tunable by hydrogenation and halogenation. The electronic structures of functionalized

graphenylenes at different concentrations of adsorbate atoms show that hydrogenated and halogenated graphenylenes exhibit a wide band gap semiconducting behavior. By controlling the type and concentration of adsorbate atoms, the band gap of graphenylene can be tuned in a wide range, 0.075 to 4.98 eV by hydrogenation and 0.024 eV to 4.87 eV by halogenation. Our present study may be useful for broadening the potential applications of functionalized graphenylenes in nanoelectronics.

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References

- K. S. Novoselov, A. K. Geim, S. V. Morozov, D. Jiang, Y. Zhang, S. V. Dubonos, I. V. Grigorieva and A. A. Firsov, *Science*, 2004, **306**, 666–669.
- A. K. Geim and K. S. Novoselov, *Nat. Mater.*, 2007, **6**, 183–191.
- A. K. Geim, *Science*, 2009, **324**, 1530–1534.
- A. S. Mayorov, R. V. Gorbachev, S. V. Morozov, L. Britnell, R. Jalil, L. A. Ponomarenko, P. Blake, K. S. Novoselov, K. Watanabe, T. Taniguchi and A. K. Geim, *Nano Lett.*, 2011, **11**, 2396–2399.
- K. S. Novoselov, A. K. Geim, S. V. Morozov, D. Jiang, M. I. Katsnelson, I. V. Grigorieva, S. V. Dubonos and A. A. Firsov, *Nature*, 2005, **438**, 197–200.
- S. V. Morozov, K. S. Novoselov, M. I. Katsnelson, F. Schedin, D. C. Elias, J. A. Jaszczak and A. K. Geim, *Phys. Rev. Lett.*, 2008, **100**, 016602.
- A. A. Balandin, *Nat. Mater.*, 2011, **10**, 569–581.
- C. Lee, X. Wei, J. W. Kysar and J. Hone, *Science*, 2008, **321**, 385–388.
- F. Liu, P. Ming and J. Li, *Phys. Rev. B*, 2007, **76**, 064120.
- P. Cudazzo, C. Attaccalite, I. V. Tokatly and A. Rubio, *Phys. Rev. Lett.*, 2010, **104**, 226804.
- R. Balog, B. Jørgensen, L. Nilsson, M. Andersen, E. Rienks, M. Bianchi, M. Fanetti, E. Lægsgaard, A. Baraldi, S. Lizzit, Z. Slijivancanin, F. Besenbacher, B. Hammer, T. G. Pedersen, P. Hofmann and L. Hornekær, *Nat. Mater.*, 2010, **9**, 315–319.
- O. Leenaerts, H. Peelaers, A. D. Hernández-Nieves, B. Partoens and F. M. Peeters, *Phys. Rev. B*, 2010, **82**, 195436.
- W. Wei and T. Jacob, *Phys. Rev. B*, 2013, **87**, 115431.
- K.-J. Jeon, Z. Lee, E. Pollak, L. Moreschini, A. Bostwick, C.-M. Park, R. Mendelsberg, V. Radmilovic, R. Kostecki, T. J. Richardson and E. Rotenberg, *ACS Nano*, 2011, **5**, 1042–1046.
- H. Gao, L. Wang, J. Zhao, F. Ding and J. Lu, *J. Phys. Chem. C*, 2011, **115**, 3236–3242.
- M. Wojtaszek, N. Tombros, A. Caretta, P. H. M. van Loosdrecht and B. J. van Wees, *J. Appl. Phys.*, 2011, **110**, 063715.
- I.-S. Byun, W. Kim, D. W. Boukhvalov, I. Hwang, J. W. Son, G. Oh, J. S. Choi, D. Yoon, H. Cheong, J. Baik, H.-J. Shin, H. W. Shiu, C.-H. Chen, Y.-W. Son and B. H. Park, *NPG Asia Mater.*, 2014, **6**, e102.
- D. Malko, C. Neiss, F. Viñes and A. Görling, *Phys. Rev. Lett.*, 2012, **108**, 086804.
- X. Niu, X. Mao, D. Yang, Z. Zhang, M. Si and D. Xue, *Nanoscale Res. Lett.*, 2013, **8**, 469.
- A. T. Balaban, C. C. Rentea and E. Ciupitu, *Rev Roum Chim*, 1968, **13**, 231–247.

- 1 21 A. T. Balaban, *Comput. Math. Appl.*, 1989, **17**, 397–416.
2 22 H. Zhu, A. T. Balaban, D. J. Klein and T. P. Živković, *J. Chem.*
3 *Phys.*, 1994, **101**, 5281–5292.
4 23 A. T. Balaban, D. J. Klein and C. A. Folden, *Chem. Phys. Lett.*,
5 1994, **217**, 266–270.
6 24 Q. Song, B. Wang, K. Deng, X. Feng, M. Wagner, J. D. Gale, K.
7 Müllen and L. Zhi, *J. Mater. Chem. C*, 2012, **1**, 38–41.
8 25 G. Brunetto, P. A. S. Autreto, L. D. Machado, B. I. Santos, R. P. B.
9 dos Santos and D. S. Galvão, *J. Phys. Chem. C*, 2012, **116**, 12810–
10 12813.
11 26 J. Koo, B. Huang, H. Lee, G. Kim, J. Nam, Y. Kwon and H. Lee, *J.*
12 *Phys. Chem. C*, 2014, **118**, 2463–2468.
13 27 J. Koo, M. Park, S. Hwang, B. Huang, B. Jang, Y. Kwon and H. Lee,
14 *Phys. Chem. Chem. Phys.*, 2014, **16**, 8935–8939.
15 28 J. Koo, H. J. Hwang, B. Huang, H. Lee, H. Lee, M. Park, Y. Kwon,
16 S.-H. Wei and H. Lee, *J. Phys. Chem. C*, 2013, **117**, 11960–11967.
17 29 Y.-X. Yu, *J. Mater. Chem. A*, 2013, **1**, 13559–13566.
18 30 G. Kresse and J. Furthmüller, *Phys. Rev. B*, 1996, **54**, 11169–
19 11186.
20 31 P. E. Blöchl, *Phys. Rev. B*, 1994, **50**, 17953–17979.
21 32 J. P. Perdew, K. Burke and M. Ernzerhof, *Phys. Rev. Lett.*, 1996,
22 **77**, 3865–3868.
23 33 H. J. Monkhorst and J. D. Pack, *Phys. Rev. B*, 1976, **13**, 5188–
24 5192.
25 34 J. Heyd, G. E. Scuseria and M. Ernzerhof, *J. Chem. Phys.*, 2003,
26 **118**, 8207–8215.
27 35 X. Wang, K. Maeda, A. Thomas, K. Takanabe, G. Xin, J. M.
28 Carlsson, K. Domen and M. Antonietti, *Nat. Mater.*, 2009, **8**, 76–
29 80.
30 36 X. Jiang, J. Nisar, B. Pathak, J. Zhao and R. Ahuja, *J. Catal.*, 2013,
31 **299**, 204–209.
32 37 X. Jiang, P. Wang and J. Zhao, *J. Mater. Chem. A*, 2015, **3**, 7750–
33 7758.
34
35